

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 06336P USA	SERIAL NO.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Aaron Scott Lukas, et al.	
		FILING DATE	GROUP

(37 CFR 1.98(b))

U.S. PATENT DOCUMENTS

EXAM- INER INITIA L		DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		5	4	5	4	9	1	5	10/3/1995	J. S. Shor, et al.	204	129.3	9/1/1993
		6	0	4	2	9	9	4	3/28/2000	J. Yang, et al.	430	296	1/8/1999
		6	0	5	4	2	0	6	4/25/2000	T. W. Mountsier	428	312.8	6/22/1998
		6	2	3	8	7	5	1	5/29/2001	T. W. Mountsier	427	574	3/16/2000
		6	2	8	4	0	5	0	9/4/2001	J. Shi, et al.	118	715	5/18/1998
		6	3	1	2	7	9	3	11/6/2001	A. Grill, et al.	428	312.6	5/26/1999
		6	4	7	5	9	3	0	11/5/2002	K. H. Junker, et al.	438	787	1/31/2000
01		0	0	1	8	1	2	9	8/30/2001	A. Shiota, et al.	428	447	1/29/2001
01		0	0	3	8	9	1	9	11/8/2001	I. L. Berry, III, et al.	428	446	3/19/2001
02		0	1	0	2	4	1	3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
02		0	1	0	6	5	0	0	8/8/2002	R. Albano, et al.	428	304.4	9/14/2001
03		0	0	3	2	3	0	0	2/13/2003	C. Waldfried, et al.	438	725	5/14/2001
03		0	0	5	4	1	1	5	3/20/2003	R. Albano, et al.	427	487	9/14/2001

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
													YES	NO
	EP	1	0	3	7	2	7	5		Europe			X	
	WO	0	0	0	2	2	4	1		World			X	
	WO	0	2	0	7	1	9	1		World			X	
	WO	02	0	6	5	5	3	4		World			X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

			A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light, Chem. Mater. 2000, 12, 3842-3847.
			M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes, Chem Mater. 2000, 12, 1591-1596.
			A. Hozumi, et al., "Micropatterned Silica Films with Ordered Nanopores Fabricated through Photocalcination, National Institute of Advanced Industrial Science & Technology, Volume 1, Number 8, August 2001.
			T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported, Mesoporous Thin Films, Chem Mater. 2000, 12, 3879-3884.
			Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.
			C. Waldfried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial citation considered. Draw line through citation if not in conf rmanc and n t consid red. Includ copy of this form with next c mmunication t applicant.